**IEUVI Resist TWG Meeting**

San Jose Convention Center, San Jose, CA
8AM-12PM, Sunday, February 26th, 2017

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| Paolo Gargini (Stanford) | Opening Remarks |
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| Oktay Yildirim (ASML) | Resist Challenges and Potential Research Areas |
| Anna Lio (Intel) | EUV Resists: When more may be less |
| Dario Goldfarb (IBM) | IBM EUV Resist-Metal Hardmask Interactions |
| Anindarupa Chunder (GlobalFoundries) | Shot Noise, LER and limitations of current EUV photoresists |
| Ruud Tromp (IBM) | TBD |
| Robert Brainard (SUNY Poly) | Electrons and holes in the EUV Exposure Mechanism |
| Alex Vaglio Pret (KLA-Tencor) | Stochastics across wavelength |
| Takahiro Kozawa (Osaka University) | Relationship between photon shot noise and secondary electron blur in line edge roughness formation |
| Kazuki Kasahara (JSR) | Nanoparticle EUV Photoresist Studies |
| Alex Robinson (University of Birmingham) | Multi Trigger Resist |
| Cliff Henderson (University of S. Florida) | Positive and Negative Tone Crosslinked Organic Molecular Resists: An Update and Outlook |
| Greg Denbeaux (SUNY Poly) | Comparison of EUV and electron reactivity for metal oxalate photoresists |

Closing remarks and discussion